

DOCKET: FI9-97-288

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

X14/C
KCM
6/24/00

INVENTOR: Christopher Obszarny) EXAMINER: P. Kim
))
SERIAL NO.: 09/116,395) ART UNIT: 2851
))
FILING DATE: July 16, 1998) DATE:
))
FOR: Apparatus and Method))
) for In-Situ Adjustment of
) light Transmission in a
) Photolithography Process
)

AMENDMENT UNDER RULE 312

Assistant Commissioner of Patents
Washington, D.C. 20231

Dear Sir:

Responsive to the Notice of Allowance dated July 20, 2000, please amend the application as follows:

In the Specification

On page 5, line 2, delete "photo-mask" and substitute therefor -- photo mask --.

On page 5, line 4, delete "Matsumoto's" and substitute therefor -- Matsumoto --.

On page 5, line 19, delete "photo lithographic" and substitute therefor
-- photolithographic --.

On page 8, line 3, after "by" delete "the".

On page 10, line 4, delete "cross section" and substitute therefor -- cross-section --.

On page 10, line 8, delete "cross section" and substitute therefor -- cross-section --.

PRODUCTION CONTROL
PUBLISHING DIVISION

AUG 15 2000

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REMARKS

Applicant notes with appreciation the allowance of this case in the Notice of Allowance mailed on July 20, 2000. In the course of preparing the application for grant,